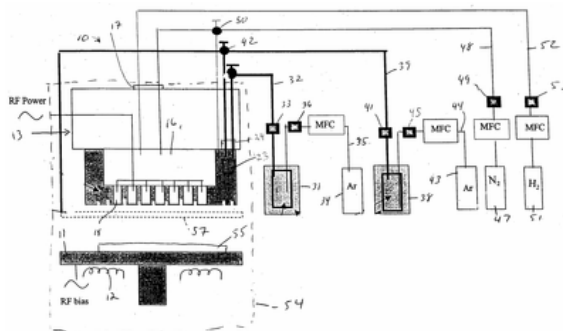


13.56 MHz Hollow Cathode Plasma Source HCD-P 100



Fig. 1: HCD-P 100

source of hydrogen gas (51). The secondary plenum is in fluid communication with a first bubbler (31) and a second bubbler (38).



Source:
<http://www.freepatentsonline.com/20050016458.html>

APPARATUS FOR PRODUCING THIN-FILM ELECTROLYTE 2003-2005

The work described below was performed using a PlasmaConsult HCD-P 100 hollow cathode plasma source.

Zhang, Ji-Guang; Meda, Lamartine;
 Maxie, Eleston
 Excellatron Solid State, LLC, Atlanta, GA (US).

Patent No.:
 US6852139B2
 US6886240B2
 US2005008772A1
 US2005016458A1
 WO2005008828A1

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Abstract

An apparatus for producing a thin film electrolyte is provided wherein a volatile lithium-containing precursor and a volatile phosphate-containing precursor are mixed into a plasma generated from a plasma source. The mixture is then deposited upon a substrate. The apparatus has a plasma source (13) having a primary plenum (16) and a secondary plenum (23). The primary plenum is in fluid communication with a source of nitrogen gas (47) and a